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2 Abstract of the Disclosure
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4 A laser direct write method creates true three dimensional
5 structures within photocerams using an focused pulsed ultraviolet
6 laser with a wavelength in a weakly absorbing region of the
7 photoceram material. A critical dose of focused laser UV light
8 selectively exposes embedded volumes of the material for subsequent
9 selective etching. The photoceram material exposure is nonlinear
10 with the laser fluence and the critical dose depends on the square
11 of the per shot fluence and the number of pulses. The laser light
12 is focused to a focal depth for selective volumetric exposure of
13 the material within a focal volume within the remaining collateral
14 volumes that is critically dosed for selecting etching and batch
15 fabrication of highly defined embedded structures.
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